



1 Inventor: Dan G. Custer et al.

2 Title: Polishing Systems, Method of Polishing Substrates, and Methods
3 of Preparing Liquids for Semiconductor Fabrication Processes

4 Assignee: Micron Technology, Inc.

5 Serial No.: 09/298,160

6 Filing Date: April 22, 1999

#11
11-8-00

7 **SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

8 **PURSUANT TO 37 C.F.R. §§1.56, 1.97 AND 1.98**

9 In compliance with 37 C.F.R. §§1.56, 1.97 and 1.98, your attention is
10 directed to the United States patents listed on the attached Form PTO-1449,
11 and copies of which are attached. No admission is made regarding whether
12 all the submitted references are prior art.

13 Citation of these references is respectfully requested.

14 Respectfully submitted,

15
16 Dated: Oct 24, 2000

15
16 Attorney: Bernard Berman

Bernard Berman

Reg. No. 37,279

WELLS, ST. JOHN, ROBERTS,

GREGORY & MATKIN P.S.

601 W. First Ave., Suite 1300

Spokane, WA 99201-3828

(509) 624-4276

10/31/2000 WKORF 00000042 09298160
01 FC:126

19 240.00 DP